

4382

## PATENT ABSTRACTS OF JAPAN

(11)Publication number : 04-152125

(43)Date of publication of application : 26.05.1992

(51)Int.Cl.

B29C 55/08  
B29C 41/12  
// B29K 1:00  
B29L 7:00

(21)Application number : 02-275293

(71)Applicant : FUJI PHOTO FILM CO LTD

(22)Date of filing : 16.10.1990

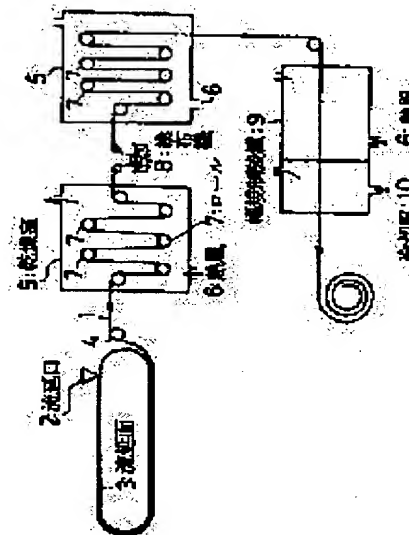
(72)Inventor : SETO KUNIHEI  
NAKAJIMA HIROSHI  
TSUJIMOTO TADAHIRO

## (54) MANUFACTURE OF SUBSTRATE FOR PHOTOGRAPHIC SENSITIZED MATERIAL

## (57)Abstract:

PURPOSE: To manufacture a film whose plane properties are not spoiled even if high-speed film making by high-temperature frying is performed, by a method wherein the film is stretched in a widthwise direction at the specific rate in a final process of the drying where a remaining solvent becomes a predetermined ratio or less.

CONSTITUTION: A cellulose triacetate dope is cast onto a casting surface 3 through a casting part 2, a film 1 formed by the same is peeled off by a peeling part 4 and the film 1 is dried by hot air 6 during running between rolls 7 within a drying chamber 5. Primer coating for photographic sensitized material is performed and dried in the drying chamber further. At a point of time when the residual solvent is about 10% or less, the film is led to a width regulating device 9, stretched by 2-6% in a widthwise direction, after the film is cooled further as it is under a tensed state and wound up. Thus, high-temperature and high-speed drying become possible, and a film making speed can be improved drastically, and after a photographic emulsion is applied to a substrate of the cellulose triacetate film, even at the time of processing into a photographic film product, no problem by processing scraps is generated.



## LEGAL STATUS

[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

BEST AVAILABLE COPY

4382

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision  
of rejection]

[Date of requesting appeal against examiner's  
decision of rejection]

[Date of extinction of right]

Copyright (C); 1998,2003 Japan Patent Office

**BEST AVAILABLE COPY**